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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
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| 09/372,879 | 08/12/1999 | STEFANOS SIDIROPOULOS | RD-036 | 1940 |

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RAMBUS INC.
4440 EL CAMINO REAL
LOS ALTOS, CA 94022

EXAMINER

FARAHANI, DANA

| ART UNIT | PAPER NUMBER |
|----------|--------------|
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2814

DATE MAILED: 01/02/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

09/372,879

Applicant(s)

SIDIROPOULOS ET AL.

Examiner

Dana Farahani

Art Unit

2814

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 18 October 2002.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-24 and 26-37 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-24 and 26-37 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
- Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- 11) ☐ The proposed drawing correction filed on _____ is: a) ☐ approved b) ☐ disapproved by the Examiner.
- If approved, corrected drawings are required in reply to this Office action.
- 12) ☐ The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

- 13) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- * See the attached detailed Office action for a list of the certified copies not received.
- 14) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
- a) ☐ The translation of the foreign language provisional application has been received.
- 15) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____.
- 4) ☐ Interview Summary (PTO-413) Paper No(s). _____.
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: _____.

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) do not apply to the examination of this application as the application being examined was not (1) filed on or after November 29, 2000, or (2) voluntarily published under 35 U.S.C. 122(b). Therefore, this application is examined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

2. Claims 1-11 are rejected under 35 U.S.C. 102(e) as being anticipated by Lee et al., hereinafter Lee (U.S. 6,329,694), previously cited.

Regarding claim 1, Lee discloses, figure 14, an integrated circuit device comprising: a conductive pad (I/O pad) to receive an input signal from an external signal line; a first doped region 61 of the first conductivity type disposed in a semiconductor substrate 50 of a second conductivity type, underlying and surrounding the conductive pad; a conductive region 65 of the first conductivity type disposed in the first doped region 61; a first tap region 66 spaced apart from and surrounding a substantial portion of the first doped region, wherein the first tap region is electrically coupled to a first supply voltage Vss; an output driver transistor, comprising segments 52, 53, and 54,

having a drain region 54 and a source region 53, wherein the drain region is electrically coupled to the conductive pad; and a second tap region 66 surrounding the output driver transistor, wherein the second tap region is electrically and physically coupled to a second supply voltage V_{ss} and the source region.

Regarding claim 2, the first and second supply voltages are ground (V_{ss}).

Regarding claim 3, first tap region completely surrounds the first doped region.

Regarding claim 4, the first tap region is a discontinuous region.

Regarding claim 5, the doping concentration of the first doped region 61 is less than the doping concentration of the conductive region 65.

Regarding claim 6, the first tap region is a third doped region and the second tap region is a fourth doped region.

Regarding claim 7, the third doped region is of an opposite conductivity type than the first doped region.

Regarding claim 8, the fourth doped region is a P type doped region.

Regarding claim 9, a portion of the first tap region is decoupled from the first supply voltage to provide a predetermined equivalent series resistance between the first doped region and the first supply voltage.

Regarding claim 10, the first tap region substantially surrounds the first doped region.

Regarding claim 11, the first tap region is a discontinuous region.

Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

4. Claims 12-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lee.

Regarding claim 12, Lee discloses the bond pad comprising conductive bonding layers 63-65; a first doped region 61 of the first conductivity type formed in semiconductor substrate 50 of the second conductivity type, underlying and surrounding the conductive bonding layer; a conductive region 65 of the first conductivity type disposed in the first doped region, the conductive region having a surface area; and a conductive tap region 66 spaced apart from and surrounding at least a portion of the first doped region, wherein a portion of the conductive tap region is electrically coupled to a supply voltage.

Lee does not disclose the surface region 65 substantially equal to the surface area of the conductive bonding layer. Note that by enlarging region 65 in order to equalize it with the conductive bonding region, region 65 would have to be enlarged to the extent that it would have make a direct connection to 64. since 64 and 65 are shorted together, the direct connection would have been another method to short these 64 and 65 together. Lee discloses at column 3, lines 8-12, that instead of metal

strapping, the shortening of the layers can be carried out directly by using semiconductor material. Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to equalize 65 to the conductive bonding layer. A mere change in the size of a component is generally recognized as being within the level of ordinary skill in the art. See *In re Rose*, 105 USPQ 237 (CCPA 1955).

Regarding claim 13, the supply voltage is a ground voltage and the conductive bonding layer includes a metal (see column 4, lines 40-55).

Regarding claim 14, the doping concentration of the first doped region is less than the doping concentration of the conductive region.

Regarding claim 15, the conductive tap region is a third doped region and is of an opposite conductivity type than the first doped region.

Regarding claim 16, a portion of the conductive tap region is decoupled from the supply voltage to provide a predetermined equivalent series resistance between the doped region and the supply voltage.

Regarding claim 17, the conductive tap region is a continuous region.

Regarding claim 18, the conductive tap region substantially surrounds the doped region.

Regarding claim 19, the conductive tap region is a discontinuous region.

Regarding claim 20, the conductive tap region substantially surrounds the doped region in a concentric-like manner.

Regarding claim 21, the conductive region is polysilicon.

Regarding claim 22, the conductive tap region is a doped layer positioned beneath the conductive region.

5. Claims 23, 24, 26, 27, and 29-37 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lee in view of the Japanese patent to Sakai et al. (document ID# 60000769), previously cited.

Regarding claims 23, 29, and 30, Lee discloses transistor layout 22 in the circuit device in figure 14 having a bond pad (I/O), the transistor layout comprising a drain region 54 of the first conductivity type formed in a semiconductor substrate 50 of the second conductivity type, the drain region being electrically coupled to the bond pad; a source region 53; and a conductive tap region 55 spaced proximal to and surrounding the drain region, wherein the conductive tap region is electrically coupled to a supply voltage V_{ss} and electrically and physically coupled to the source region.

Lee neither discloses the source and the drain region being of opposite conductivity types, nor discloses a section of the conductive tab region is structurally integrated with the source region.

The Japanese patent discloses, in figure 4c, wherein source and drain regions have both conductivity types regions in order to convey data (see the paragraph titled CONSTITUTION). Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to make the source and the drain region of the opposite conductivity type, as the Japanese patent teaches, in order to be able to use Lee's invention in a memory device.

Lee discloses at column 3, lines 8-12, that shortening of the layers can be carried out by semiconductor, instead of the strapping shown in the figures. Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to integrate the source and the tap region, as Lee teaches, in order to eliminate the need for metal strapping.

Regarding claim 24, the supply voltage is coupled to a ground voltage V_{ss} .

Regarding claim 26, the conductive tap region 55 is spaced proximal to and completely surrounds the drain region.

Regarding claim 27, the conductive tap region is a discontinuous region.

Regarding claims 31-37, Lee does not disclose in the embodiment of figure 14 that a tap region spaced proximal to the drain region and electrically decoupled from the supply voltage and the conductive tap region.

Lee discloses in the embodiment of figure 21 that tap region 106 is decoupled from the conductive tap region and the supply voltage. It would have been within the level of ordinary skill in the art to make region 66 spaced proximal to the drain region and electrically decoupled from the supply voltage and the conductive tap region in order to make the embodiment shown in figure 21 of Lee.

6. Claim 28 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lee as applied to claim 23 above, and further in view of Microelectronic Circuits by Sedra and Smith.

Lee discloses in figure 10, a plurality of source regions 13 and 23, where one of the source region of the plurality of source regions being electrically and physically

coupled to the conductive tap region 25; a plurality of drain regions 24 and 14, where one of the drain region of the plurality of drain regions being electrically coupled to the bond pad; and wherein the conductive tap region is spaced proximal to and surrounds at least one drain region 24 of the plurality of drain regions.

Lee does not disclose the other drain and source regions are connected to the Vcc, or ground pad.

Sedra and Smith reference discloses in page 358, figure 5.3, that a source is grounded and a voltage is applied to a drain. It would have been obvious to one of ordinary skill in the art at the time of the invention to ground either source or drain of the MOSFET transistor, as the Sedra and Smith reference teaches, in order to interchange the source and the drain regions.

Response to Arguments

7. Applicants' arguments filed 10/18/02 have been fully considered but they are not persuasive.

Applicants argue that the conductive pad of the claimed invention is a "conductive bond pad layer" and it is disposed above a doped region, which in turn forms a PN junction with the substrate (see page 11 of applicants' response to the previous Office Action). Applicants further allege that Lee conductive pad is merely a schematics input and output pad, and therefore, does not resemble any thing close to the pad of the instant application. This is not found persuasive, since Lee discloses in figure 14 that the I/O pad is connected to doped region 63. Therefore, 63 is essentially

part of the I/O pad, which in fact make a PN junction on the substrate. Regardless, claim 1 merely recites a bond pad structure, not the parts of the specification applicants point out in the argument. Although the claims are interpreted in light of the specification, limitations from the specification are not read into the claims. See *In re Van Geuns*, 988 F.2d 1181, 26 USPQ2d 1057 (Fed. Cir. 1993).

In regard to applicants' argument that bonding layer 63-65 cannot be conductive bonding layer, rather they are source, drain, and pickup regions, the fact that they are source, drain, and pickup regions does not have any effect on those regions not being a conductive bonding layer, since they are inherently constitute a conductive bonding layer (that is they are conductive and can have external connections).

Regarding applicants' argument that it would not have been obvious to equalize region 65 to the conductive bonding layer, the Office maintain the obviousness rejection for the following reason. Note that by enlarging region 65 in order to equalize it with the conductive bonding region, region 65 is enlarged to the extent that it would make a direct connection to 64. since 64 and 65 are shorted together, the direct connection would have been another method to short these 64 and 65 together. In fact, Lee discloses at column 3, lines 8-12, that instead of metal strapping, the shortening of the layers can be carried out directly by using semiconductor material. Therefore, one would have been motivated to change the size of region 65. A mere change in the size of a component is generally recognized as being within the level of ordinary skill in the art. See *In re Rose*, 105 USPQ 237 (CCPA 1955). This reasoning also applies to the argument in regard to claim 23, in which applicants argue that the limitation of: "a

section of the conductive tab region is structurally integrated with the source region" is not rendered obvious by Lee, and therefore the reasoning will not be repeated.

Regarding applicants' argument that the Japanese patent, issued to Sakai, does not disclose or suggest a transistor having a source/drain region with both conductivity types present, the Office notes that in figure 4c, Sakai discloses a transistor with both conductivity types present, further discloses that by doing so both regions (of conductivity type) can be used to convey information to the transistor (see the paragraph titled CONSTITUTION). Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to make both conductivity types to be present in the source/drain region of the Lee reference, as Sakai teaches, in order to be able to use Lee's structure in a memory device.

Conclusion

8. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

Art Unit: 2814

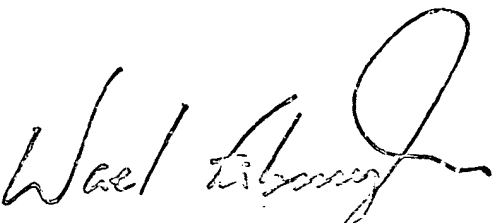
the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dana Farahani whose telephone number is (703)305-1914. The examiner can normally be reached on M-F 8:00AM - 5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (703)308-4918. The fax phone numbers for the organization where this application or proceeding is assigned are (703)872-9318 for regular communications and (703)872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Dana Farahani
December 28, 2002


SUPERVISORY PRIMER EXAMINER
TECHNOLOGY CENTER 2800